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(54) Title: INSPECTION OF LITHOGRAPHIC LAYERS AND DYNAMIC DATA VIA INLINE METROLOGY

(57) Abstract: Aspects of disclosure provide a method for processing an apparatus. The method includes determining one or more altered electrical connections based on an offset between a designed component and an altered component disposed on a substrate. The method includes depositing a photoresist over the substrate and developing the photoresist to form one or more developed regions and one or more undeveloped regions. One of the one or more developed regions or the one or more undeveloped regions of the photoresist are removed to form an altered electrical connection template. The altered component and the altered electrical connection template are scanned to identify one or more misaligned regions of the altered electrical connection template. At least a portion of the altered electrical connections template is removed.

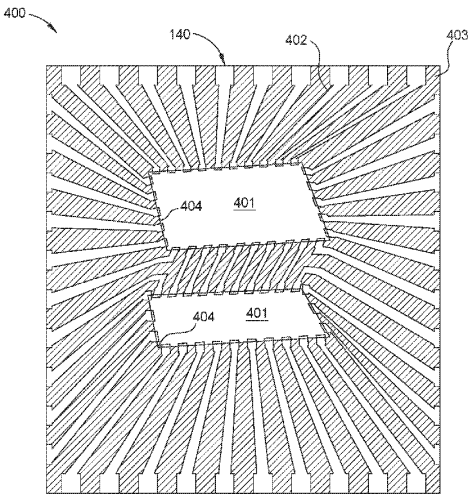


FIG. 4

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